

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	5161	electrode and (sacrificial or polyimide) and membrane and (etch\$4 or pattern\$4) and (pad or contact)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:42
L2	451046	MEMS or "micro electromechanical system"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:38
L3	1218	1 and 2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:39
L4	111	3 and (flexible near substrate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:40
L5	595	electrode same (sacrificial or polyimide) same (membrane or SiN or "silicon nitride") same (etch\$4 or pattern\$4) same (pad or contact)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:48
L8	1499	electrode and (sacrificial or polyimide) and (membrane or SiN or "silicon nitride") and actuator and (etch\$4 or remov\$4) and pad	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:45
L9	795	8 and 2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:45
L10	1170	((257/254) or (257/416) or (257/417)).CCLS.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/18 14:46

## EAST Search History

L11	1501	((438/52) or (438/53) or (438/458)). CCLS.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/18 14:47
L12	1173	((438/745) or (438/750)).CCLS.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2006/07/18 14:47
L13	417	electrode same (sacrificial or polyimide) same (membrane or SiN or "silicon nitride") same (etch\$4 or pattern\$4) same (cavity or opening or trench)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/07/18 14:48
L14	2	(sacrificial and membrane and (flexible adj substrate) and electrode and pattern\$4 and pad ).clm.	US-PGPUB	OR	ON	2006/07/18 14:50